

**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants	Ishiduka, et al.	Examiner:	Johnson, Connie P.
Application No.:	10/591,718	Group Art Unit:	1722
Confirmation No:	3280	Docket:	1608-7 PCT/US/RCE II
Filed:	September 5, 2006	Dated:	July 26, 2011
For:	POSITIVE-TYPE RESIST COMPOSITION FOR LIQUID IMMERSION LITHOGRAPHY AND METHOD FOR FORMING RESIST PATTERN		

Commissioner for Patents  
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Alexandria, VA 22313-1450

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Dated: July 26, 2011

Signature: Marcy Mancuso /Marcy Mancuso/

**AMENDMENT AND RESPONSE PURSUANT TO 37 C.F.R. §1.111**

Sir:

This is in response to the Office Action dated April 26, 2011, the due date for which is July 26, 2011. Entry of the amendments and reconsideration are respectfully requested.

**Amendments to the Claims** begin on page 2 of this submission.

**Remarks** begin on page 9 of this submission.